



IFu

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Toru YAMADA

Group Art Unit: 1792

Application No.: 10/582,802

Examiner: F. HITESHEW

Filed: June 14, 2006

Docket No.: 136170

For: VAPOR PHASE GROWTH APPARATUS AND METHOD OF FABRICATING
EPITAXIAL WAFER

REQUEST FOR RECONSIDERATION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In reply to the September 17, 2008 Office Action, reconsideration of the rejection and objections is respectfully requested in light of the following remarks.

Claims 1-15 are pending in this application. Claims 5 and 10-15 are allowed and claims 1-4 have been rejected. Claims 7-9 are objected to.

The rejection of claims 1-4 and 6 as being anticipated by JP '939 is respectfully traversed.

Attached to this response is a copy of the English-language translation of JP 2000-331939 obtained from the Japanese website. Also attached is Attachment 1 which shows the axis set forth in the next to the last paragraph in Applicant's claim 1.

Applicant respectfully submits that claim 1 is not anticipated by '939. The Examiner has cited guide plates (11a to 11f) as rectifying gas guided into the process chamber (2) and guide it to a specific region on the surface of the wafer W on the placement part (7a). This